

NIOBIUM OXIDE SINTERED COMPACT, SPUTTERING TARGET
FORMED FROM SAID SINTERED COMPACT, AND METHOD OF PRODUCING
NIOBIUM OXIDE SINTERED COMPACT

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ABSTRACT

The present invention provides a niobium oxide sintered compact having a composition of NbO_x ($2 < x < 2.5$), and specifically provides a niobium oxide sintered compact which can be applied to a sputtering target for forming a high-quality resistance change layer for use in ReRAM. In particular, the present invention aims to provide a high-density niobium oxide sintered compact suitable for stabilizing the sputtering process.

15 Fig. 1